

MAY 30 2006

Attorney Docket No.: MEMS-0196-US

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): BROWN

Conf. No.: 5924

Application No.: 10/665,531

Art Unit: 1756

Filed: 22 Sep 2003

Examiner: Chacko Davis, D

Title: LITHOGRAPHY PROCESS TO REDUCE
SEAM LINES IN AN ARRAY OF
MICROELEMENTS PRODUCED FROM A
SUB-MASK AND A SUB-MASK FOR USE
THEREOF

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY AND/OR AMENDMENT UNDER 37 C.F.R. §§ 1.111

Sir:

In response to the Office Action of November 28, 2005, please amend the
above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page
2 of this paper.

Remarks/Arguments begin on page 11 of this paper.